

Sir:

PATENT Customer No. 22,852 Attorney Docket No. 04329.2620-01

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IIIIe	Application of	<i>)</i>
Hiroshi NOMURA et al.		) Group Art Unit: 2851
Application No.: 10/657,251		) Examiner: Alan A. MATHEWS
Filed:	September 9, 2003	) )
For:	EVALUATION MASK, FOCUS MEASURING METHOD AND ABERRATION MEASURING METHOD	) Confirmation No.: 4036 ) ) )
P.O.	missioner for Patents Box 1450 andria, VA 22313-1450	· . · · · · · · · · · · · · · · · · · ·

## **AMENDMENT**

In reply to the Office Action mailed December 16, 2004, the period of response extending through March 16, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims in this paper.

Remarks/Arguments follow the amendment sections of this paper.